CLASSIFICATION SECRET CENTRAL INTELLIGENCE AGENCY REPORT RMATION REPORT CD NO DATE DISTR COUNTRY East Germany 10 January 1955 NO. OF PAGES SUBJECT Germanium and Development NO OF ENCLS PLACE **4CQUIRED** 25X1 SUPPLEMENT TO DATE OF REPORT NO. NFO 25X1 POCUMENT CONTAINS INFORMATION AFFECTING THE IT UNITED STATES, WITHIN THE MEASURE OF TITLE 46, OF THE 9 S CODE, AS AGENDED ITS TRAMB OF ITS COMTENTS TO OR RECEIPT BY AN GRAM DEIDITED BY LAW THE REPRODUCTION OF THIS P NEVALUATER INFORMATION

loped in Ea ny by VEB Werk fuer Transistors have technik "d Ossietzky" (formerly Bauelemente der N EB Werk fu eldewesen (former OSW) Dralowid), in Tel in Berlin-Oberscho Some tr rescarch has also been carried out in the Acad **y** Institute earch on the Physics of Solids in Berlin-Buch.

The OSW enterprise obt the order earch and development of transistors from the ets while iterprise was still under rge see, up to 100,000 Eter the project was in-SAG administration. iets inve DME per year, in the pment pro two parallel Work Groups, itiated by the Sov s carried one working for th and the of carrying out the same develo ment for the man govern Difficulties arose from the fact that the ject was g by strict secrecy measures and details of not allowe divulged

These difficulties, howto anyone not in the wo ed. Trans velopment in the OSW ever were somehow enter rise at that upervised ingel (fnu). No progress was made unde ervision, i made after Dr. Bingel wa d from his ons and after the OSW enterprise was retu erman admi ion. In late 1953, the

ise and cut off all mon-Soviets withdrew th er from the etary allocations f At Soviet i ce, transistor develo :ment was to be cond exclusivel as Falter, Dralowid plant, where, in the meantime, Dr the research and development of the fir de conside rogress in the development of the devices W research inder the supervision of Dr. Richter (fnu), continued insistor development on its own and in the late summer of 1954 succe ded in completing laboratory

samples of transistors. In September 1954, the East German gover ment was requested to decide whether transistor production should be carried out at Drahowid or OSW or at both plants. In order to decide this a session of "Arbeitskreis Richthalbleiter" was called, with representatives of the State Planning Commission present.

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Both enterprises demonstrated sample circuits in which transistors produced by them were used. As a result of this test, a preliminary decision was reached that the manufacture of transistors would in the future be carried out by the Dralowid plant only and that all monetary allocations for this urpose by the East German government would go there. This decision, however, is subject to revision by the government.

- The Dralowid plant, which started transistor development much later than the CSW enterprise, succeeded in producing development samples during the first part of 1,54. The plan in this enterprise was to develop transistors of stable qualities by the end of 1954, so that full-fledged production could begin in 1955. As of carly November 1954 this goal had been reached. Production of transistors at Dr. lowid was to start soon, possibly even in 1914. Dralowid was able to start full-fledged production of transistors up to a maximum frequency of 10 mcs with an output amplification, between 100 and 1,000 mcs.
- 4. In addition to the work on germanium transistor "escribed above, Dr. Falter's department his also carried cut development of silicon transistors, but this has not progressed beyond it's initial stages. It is of early Novemb r 1954, it had been abandoned entirely and work was exclusively concentrated on germanium transistors. The reasons for discontinuation of silicon transistor development were:
 - a. Dralowid had enough germanium and hoped to be able to obtain sufficient amounts in the future for production. As of early November 1954, the plant had about one kilogram of germanium of 99.99% purity, delivered by the firm Franke in Frankfurt/ Main. This firm had also made ger anium deliveries to Dralowid previously.
 - b. Because of the higher merting point of silicon as compared with that of termanium, the making of very pure solicon monocrystals presents more technological difficulties than the making of germanium monocrystals.
- The transistors so far developed in East Germany are all point cont ct transistors. As of early November 1954, Dr. Falter was also engaged in the levelopment of junction type transistors, but this work has so far been unsuccessful. Dr. Falter had only succeeded in completing the first step in this direction by developing layer rectifiers (Flacchengleichrichter) from n-germanica and indiam. These rectifiers will go into full-scale production. Trey can be operated with inverse voltage up to 1,000 volts and they h vo strong photo-effects, i.e. the reversed current is increased through illumination with light beyond the limit of visibility up to try micron wave lengths. r. Falter furthermore tried to develog junction-type tr naistors by v perilang elements of the third group upon both sides of neger: unium and elements of the fifth group, upon both sides of pegermanium crystals in it's vacuum, and by having these elements diffused into the crastel. at tem eratures just below the melting point of germanium. These at empts, ho ever, failed because Dr. Falter as not able to obtain well-defined inversion layers in this way. The attempts at Dr. lowid to develor james tion-type Germanium transistors were to be continued. Dr. Filter is assisted inthis work by mathematician G. Raabe and physicist Bl nkeapurg (r.u).

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6. Transistor research corried but in the Academy Institute for Medicine and Biology in Berlin-Buch up to early November 1954 had not progres ed beyond the stage of prescring pure germanium monocrystals suitable for use as transistors. The Electronics Department of this institute was engaged in early November 1954 in measuring the curity and other qualities of the monocrystals. The institute had small quantities of chemically pure germanium which were provided by the Dralowid plant.

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Approved For Release 2007/11/07: CIA-RDP80-00810A005600260009-6 CLASSIFICATION SECRET CENTRAL INTELLIGENCE AGENCY REPORT INFORMATION REPORT CD NO. COUNTRY DATE DISTR. East Germany 10 January 1955 3 NO. OF PAGES SUBJECT Germanium and Silicon Transistor Development 25X1 NO. OF ENCLS. PLACE (LISTED BELOW) **ACQUIRED** SUPPLEMENT TO DATE OF REPORT NO. INFO.

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1. Transistors have been developed in East Germany by VEB Werk fuer Bauelemente der Nachrichtentechnik "Carl von Ossietzky" (formerly Dralowid), in Teltow, and VEB Werk fuer Fernmeldewesen (former OSW) 25X in Berlin-Oberschoeneweide. Some transistor research has also beem carried out in the Academy Institute for Research on the Physics of Solids in Berlin-Buch.

2. The OSW enterprise obtained the order for research and development of transistors from the Soviets while the enterprise was still under SAG administration. The Soviets invested large sums, up to 100,000 DME per year, in this development project. After the project was in-

DME per year, in this development project. After the project was initiated by the Soviets it was carried out in two parallel Work Groups, one working for the Soviets and the other one carrying out the same development for the East German government. Difficulties arose from the Soviet project was guarded by the project was guarded by the source of the

Soviet project was guarded by Atlanta Socrecy and of it were not allowed to be not engaged in the work. These distinction, however were somehow circumvented. Transistor development in the OSW enterprise at that time was supervised (fau). To pro-ress was made under his supervisit after Dr. Bingel was relieved from the OSW (fau). No pregenterprise was returned to German administration. In late 1953, the enterp...
Soviets withdrew there etary allocations for it. Soviets withdrew their order from the enterprise and cut off all monviet insistence, transistor developsively in the Dralowid plant, me, Dr. Ma Ater, head of the research and the firm, had ade considerable progress in the development of the firm, had ade considerable progress in the development of the devices. The OSW research team under the supervision of Dr. Richter (fnu), however, continued transition development of an and in the late summer of 1954 succeeded in completing samples of transistors. In September 1954, The East ernant was requested to decide wheteer transistor production should be carried out at Drawlowid or OSW or at both plants. In order to de-

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5.	Transistor research carried out inthe Academy Institute for Medicane and Riology in Berlin-Buch up to early Nevember 1954 had not progressed beyond the stage of preparing pure germanium monecrystals suitable for use as transistors. The Electronica Department of this institute was engaged in early Nevember 1954 in measuring the purity and other qualities of the memocrystals. The institute had small quantities of chemically	
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